

L Number	Hits	Search Text	DB	Time stamp
-	68	(plasma adj generators!) and 118/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 13:44
-	5	(plasma adj generators!) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 13:19
-	3	(ECR near2 (several or plural\$4 or multiple or second)) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 13:23
-	78	(ald or ale or sequential adj (chemical adj vapor or CVD)) and (117/\$4.ccls. or 118/\$4.ccls.) and plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 14:02
-	113	plasma adj (ald oe ale or atomic adj layer or sequential adj chemical or sequential adj CVD)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 14:00
-	10	plasma adj (ald or ale or atomic adj layer or sequential adj chemical or sequential adj CVD)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 14:00
-	42	(ald or ale or sequential adj (chemical adj vapor or CVD)) same plasma and (117/\$4.ccls. or 118/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 14:23
-	80	(ald or ale or sequential adj (chemical adj vapor or CVD)) same apparatus and (422/\$4.ccls. or 427/\$4.ccls. or 118/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 14:47
-	30	(ald or ale or sequential adj (chemical adj vapor or CVD)) same apparatus and (422/\$4.ccls. or 427/\$4.ccls. or 118/\$4.ccls.) and (supply or precursor or reactant) near4 control\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 14:49
-	30	(ald or ale or sequential adj (chemical adj vapor or CVD)) same apparatus and (422/\$4.ccls. or 427/\$4.ccls. or 118/\$4.ccls.) and (supply or precursor or reactant) near4 control\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 15:06
-	114	(plasma adj generat\$4 or ECR) near3 two and (118/\$4.ccls. or 422/\$4.ccls. or 427/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 15:26
-	102	(plasma adj generat\$4 or ECR) near3 remote and (118/\$4.ccls. or 422/\$4.ccls. or 427/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 15:51
-	105	(plasma adj generat\$4 or ECR) near3 (separate or individual) and (118/\$4.ccls. or 422/\$4.ccls. or 427/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 15:55

-	35	alternately adj suppl\$4 and (ale or ald)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 17:08
-	19	sequential\$4 adj (CVD or chemical adj vapor) and (118/\$4.ccls. or 422/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/04 16:31
-	10	alternately adj suppl\$4 and (ale or ald) and (118/\$4.ccls. or 422/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/06 11:19
-	51	(plasma same activat\$4 same deposit\$4) and (117/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/06 13:31
-	56	(plasma same activat\$4 same temperature) and (117/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/06 13:38
-	75	heat\$4 near2 surround same susceptor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/06 13:42